

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

I. SEKI et al

Serial No.

Filed: January 10, 2001

For: ION IMPLANTATION EQUIPMENT AND  
IMPLANTATION METHOD THEREOF

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents  
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified  
patent application as follows.

IN THE CLAIMS

Please amend claim 3 as follows.

3. (Amended) An ion implantation equipment as defined  
in claim[s] 1 [and 2], wherein

said scanning means for putting together a scanning  
surface of said ion beam with a deflection surface of said ion  
beam deflected by said mass separation means.